ABSTRACT OF THE DISCLOSURE

     A charged-particle beam exposure apparatus for
exposing a member to be exposed to a charged particle
beam with a pattern includes memories (902 - 905) for
5 storing a plurality of control data for controlling
reference dose data of the charged particle beam in
accordance with the incident position of the charged
particle beam on the member to be exposed, a selector
(907) for selecting any one of the plurality of
10 control data stored in the memories, and an exposure
unit for controlling the reference dose data of the
charged particle beam for each irradiation position
on the basis of the control data selected by the
selector, thereby exposing the member to be exposed
15 with the pattern. The charged-particle beam exposure
apparatus rapidly performs proper proximity effect
correction to expose the member to be exposed with
the pattern.